## A) Amendments to the claims:

1. (currently amended) A saponified poly(vinyl acetate)-based photosensitive resin characterized by having a structural unit represented by formula (1):

(wherein R<sub>1</sub> represents H or Me; R<sub>2</sub> represents a linear or branched C2-C10 alkylene group; n is an integer of 1 to 3; X represents

m is an integer of 0 to 6; and Y represents an aromatic ring or a single bond).

- 2. (original) A photosensitive resin composition comprising a photosensitive resin according to claim 1.
- 3. (original) A photosensitive resin composition according to claim 2, which further comprises at least one photopolymerization initiator.
- 4. (currently amended) A photosensitive resin composition according to claim 2 or 3, which further comprises water.
- 5. (currently amended) A method for forming a hydrogel comprising subjecting a photosensitive resin composition as recited in any of claims 2 to 4 to photopolymerization.
  - 6. (currently amended) A compound represented by formula (2):

(wherein R<sub>1</sub> represents H or Me; R<sub>2</sub> represents a linear or branched C2-C10 alkylene group; X represents

Applicant: Seigo Yamada, Et. AL. Serial No. Unknown Filing Date: June 10, 2005

m is an integer of 0 to 6; and Y represents an aromatic ring or a single bond).

7. (currently amended) A compound represented by formula (3):

(wherein R<sub>1</sub> represents H or Me; R<sub>2</sub> represents a linear or branched C2-C10 alkylene group; X represents

$$\begin{array}{c|c} & H_2 \\ \hline C & C \\ C & C \\ \hline C & C \\ C & C \\ \hline C & C \\ C & C \\ \hline C & C \\ C & C \\ \hline C & C \\ C & C \\ \hline C & C \\ C & C \\ \hline C & C \\ C & C \\ \hline C & C \\ C & C \\ \hline C & C \\ C & C \\ \hline C & C \\ \hline C & C \\ C & C \\ \hline C & C \\ C & C \\ \hline C & C \\ C$$

m is an integer of 0 to 6; Y represents an aromatic ring or a single bond; and each of R<sub>3</sub> and R<sub>4</sub> represents a C1-C3 alkyl group).

- 8. (new) A photosensitive resin composition according to claim 3, which further comprises water.
- 9. (new) A method for forming a hydrogel comprising subjecting a photosensitive resin composition as recited in claim 3 to photopolymerization.
- 10. (new) A method for forming a hydrogel comprising subjecting a photosensitive resin composition as recited in claim 4 to photopolymerization.